

## **ABSTRACT OF THE DISCLOSURE**

5        Provided herein is a method for cleaning a process  
chamber for semiconductor and/or flat panel display  
manufacturing. This method comprises the steps of converting a  
non-cleaning feed gas to a cleaning gas in a remote location and  
then delivering the cleaning gas to the process chamber for  
cleaning. Such method may further comprise the step of  
10    activating the cleaning gas outside the chamber before the  
delivery of the gas to the chamber. Also provided is a method of  
eliminating non-cleaning feed gas from the cleaning gas by cryo  
condensation.